

AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior versions, and all prior listings, of claims in the application:

Listing of the Claims:

Claims 1 and 2 (Cancelled).

3. (Currently Amended) ~~The~~ A photosensitive resin composition according to claim ~~2~~ 11, wherein said diamine is a diaminopolysiloxane.

4. (Currently Amended) ~~The~~ A photosensitive resin composition according to claim ~~4~~ 11, wherein said transmittance is in a range of 40%-68%.

Claims 5-9 (Cancelled).

10. (Currently Amended) A photosensitive resin composition which comprises (1) a polyimide precursor ~~formed from~~ produced using (a) an oxydiphthalic acid or acid anhydride thereof as a reactant for forming the polyimide precursor, and (b) at least one diamine selected from the group consisting of diaminodiphenyl ether, diaminodiphenyl sulfone, metaphenylene diamine, p-phenylenediamine, p-xylylenediamine, diaminonaphthalene, dimethylbenzidine, dimethoxybenzidine, diaminodiphenylmethane, diaminodiphenylsulfide, benzophenonediamine, bis((aminophenoxy) phenyl)sulfone, hexafluoro-bis(aminophenyl)propane, bis((aminophenoxy)phenyl)propane, dimethyl-

~~diaminophenyl-methane, tetramethyl-diaminodiphenylmethane,~~
~~bis((aminophenoxy)phenyl) sulfone, bis(aminophenyl)propane and~~
~~diaminopolysiloxanewith a diamine,~~ (2) an addition-polymerizable compound, and
(3) a photoinitiator, and which is adapted to be exposed and developed using an i-
line stepper which uses monochromatic light, the polyimide precursor being such
that a 20 μm thick film thereof has a transmittance, at 365nm, of at least 40%.

11. (Original) A photosensitive resin composition according to claim 10,
wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

12. (Original) A photosensitive resin composition according to claim 11,
wherein said diamine is a diaminodiphenyl ether.

13. (Original) A photosensitive resin composition according to claim 10,
wherein said diamine is a diaminodiphenyl ether.

Claims 14-16 (Cancelled).

17. (Currently Amended) A photosensitive resin according to claim ~~14~~ 13,
wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl
ether, 2,4'-diaminodiphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diamino-
diphenyl ether.

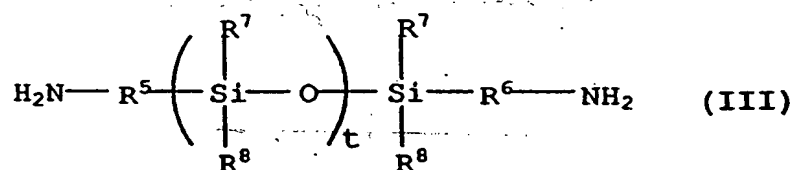
Claim 18 (Cancelled)

19. (New) A photosensitive resin composition according to claim 10, wherein said at least one diamine is selected from the group consisting of 4, 4'-diaminodiphenyl ether, 2, 4'-diaminodiphenyl ether, 3, 4'-diaminodiphenyl ether, 3, 3'-diaminodiphenyl ether, 4, 4'-diaminodiphenyl sulfone, 3, 3'-diaminodiphenyl sulfone and metaphenylenediamine.

20. (New) A photosensitive resin composition according to claim 19, wherein said at least one diamine is selected from the group consisting of 3, 4'-diaminodiphenyl ether, 3, 3'-diaminodiphenyl sulfone, 4, 4'-diaminodiphenyl sulfone and methaphenylenediamine.

21. (New) A photosensitive resin composition according to claim 10, wherein the at least one diamine includes a diaminopolysiloxane represented by the formula (III):

(III):



wherein R^5 and R^6 each represent a divalent hydrocarbon group; R^7 and R^8 each represent a monovalent hydrocarbon group; each of R^5 , R^6 , R^7 and R^8 may be the same or different; and t represents an integer of 1 to 5.

22. (New) A photosensitive resin composition according to claim 21, wherein said divalent hydrocarbon group has 1 to 3 carbon atoms, and said monovalent hydrocarbon group has 1 to 3 carbon atoms.

23. (New) A photosensitive resin composition which comprises (1) a polyimide precursor produced using (a) an oxydiphthalic acid or acid anhydride thereof as a reactant for forming the polyimide precursor, and (b) at least one diamine including a hydroxyl group-containing diamine, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light, the polyimide precursor being such that a 20 μm thick film thereof has a transmittance, at 365 nm, of at least 40%.